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16/073874  
02/14/02

PATENT NUMBER and  
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM 10073874	FILING DATE 02/14/2002	CLASS 430	SUBCLASS 5	GAU 1756	EXAMINER RO-ASCO
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\*\*APPLICANTS: Shoki Tsutomu; Hosoya Morio;

\*\*CONTINUING DATA VERIFIED:

*AL NONE*

\*\* FOREIGN APPLICATIONS VERIFIED:

JAPAN 37034/2001 02/14/2001 *AL*

PG-PUB ☐ DO NOT PUBLISH ☐ RESCIND ☐

Foreign priority claimed ☒ yes ☐ no

35 USC 119 conditions met ☒ yes ☐ no

Verified and Acknowledged Examiners's initials *AL*

ATTORNEY DOCKET NO

Q68554

TITLE : Reflection type mask blank for EUV exposure and reflection type mask for EUV exposure as well as method of producing the mask

U.S. DEPT. OF COMM./PAT. & TM.-PTO-436L (Rev. 12-94)

<b>NOTICE OF ALLOWANCE MAILED</b>		<b>CLAIMS ALLOWED</b>	
		Total Claims	Print Claim for 0.0
Assistant Examiner		<b>DRAWING</b>	
		Sheets Drwg.	Figs. Drwg.
Primary Examiner		Print Fig.	
<input type="checkbox"/> <b>TERMINAL DISCLAMER</b>		Application Examiner	
<b>PREPARED FOR ISSUE</b>			
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